

APPENDIX B
VERSION WITH MARKINGS TO SHOW CHANGES MADE
37 C.F.R. § 1.121(b)(iii) AND (c)(ii)

CLAIMS:

1. (AMENDED) A substrate method for cleaning a substrate by supplying a cleaning solution thereto, comprising the steps of:
supplying said cleaning solution having ozone dissolved therein to said substrate; and
subsequently irradiating said cleaning solution supplied to said substrate with ultraviolet light.
9. (AMENDED) A substrate treating apparatus comprising:
a support [means for supporting] that supports a substrate;
a cleaning solution supply [means for supplying] that supplies a cleaning solution having ozone dissolved therein to said substrate; [and]
an ultraviolet [emitting means for emitting] emitter that emits ultraviolet light to said substrate; and
[wherein] a control which controls the ultraviolet emitter so that, during a cleaning process in which said cleaning solution is supplied from said cleaning solution supply [means] to said substrate supported by said support [means], said ultraviolet [emitting means] emitter emits ultraviolet light to said cleaning solution supplied to said substrate.
10. (AMENDED) An apparatus as defined in claim 9, wherein the ultraviolet light [emitted from said ultraviolet light emitting means] has a wavelength in a range of 242.4 to 300nm.
11. (AMENDED) An apparatus as defined in claim 9, wherein said cleaning solution [has a] includes a base[added thereto].

17. (AMENDED) A substrate treating method for removing film from a substrate by supplying a treating solution thereto, comprising the steps of:

supplying said treating solution having ozone dissolved therein to said substrate; and
subsequently irradiating said treating solution supplied to said substrate with ultraviolet light.

25. (AMENDED) A substrate treating apparatus for removing film from a substrate by supplying a treating solution thereto, comprising:

a support [means for supporting] that supports said substrate;
a treating solution supply [means for supplying] that supplies said treating solution having ozone dissolved therein to said substrate; [and]
an ultraviolet [emitting means for emitting] emitter that emits ultraviolet light to said substrate; and

[wherein] a control that controls the ultraviolet emitter so that, during a film removing process in which said treating solution is supplied from said treating solution supply [means] to said substrate supported by said support[means], said ultraviolet [emitting means] emitter emits ultraviolet light to said treating solution supplied to said substrate.

26. (AMENDED) An apparatus as defined in claim 25, wherein the ultraviolet light [emitted from said ultraviolet light emitting means] has a wavelength in a range of 242.4 to 300nm.